

L Number	Hits	Search Text	DB	Time stamp
-	10	(148/437,415.ccls. or 420/548,552.ccls.) and (sc or scandium or si or silicon or ti or titanium or hf or hafnium) and (ecae or ((equal or channel) near2 (extrusion or extruded or extrude))) and (grain or size near2 ("mu.m" or "mu" or "mu." or micron or micrometer or ".mu.m" or ".mu." or "mum" or mu.m or \$1"mu.m"))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/20 17:04
-	15	((148/437,415.ccls. or 420/548,552.ccls.) and (sc or scandium or si or silicon or ti or titanium or hf or hafnium) and (grain or size near2 ("mu.m" or "mu" or "mu." or micron or micrometer or ".mu.m" or ".mu." or "mum" or mu.m or \$1"mu.m")) and ((sputter\$4 or physical or vapor) near3 target)) not ((148/437,415.ccls. or 420/548,552.ccls.) and (sc or scandium or si or silicon or ti or titanium or hf or hafnium) and (ecae or ((equal or channel) near2 (extrusion or extruded or extrude))) and (grain or size near2 ("mu.m" or "mu" or "mu." or micron or micrometer or ".mu.m" or ".mu." or "mum" or mu.m or \$1"mu.m"))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/20 16:24
-	4	"6423161"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/20 16:24
-	1	2001-316250.NRAN.	DERWENT	2003/09/20 16:24
-	24	(148/437,415.ccls. or 420/548,552.ccls.) and (sc or scandium or si or silicon or ti or titanium or hf or hafnium) and (grain or size near2 ("mu.m" or "mu" or "mu." or micron or micrometer or ".mu.m" or ".mu." or "mum" or mu.m or \$1"mu.m")) and ((sputter\$4 or physical or vapor) near3 target)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/20 18:54
-	11	(148/437,415.ccls. or 420/548,552.ccls.) and (sc or scandium or si or silicon or ti or titanium or hf or hafnium) and ((grain or size) near2 ("mu.m" or "mu" or "mu." or micron or micrometer or ".mu.m" or ".mu." or "mum" or mu.m or \$1"mu.m")) and ((sputter\$4 or physical or vapor) near3 target)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/20 16:42
-	45	((al or aluminum) near2 (alloy or base or based or balance)) and (sc or scandium or si or silicon or ti or titanium or hf or hafnium) and ((grain or size) near2 ("mu.m" or "mu" or "mu." or micron or micrometer or ".mu.m" or ".mu." or "mum" or mu.m or \$1"mu.m")) and ((sputter\$4 or physical or vapor) near3 target) and (148/\$.ccls. or 420/\$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/20 18:45
-	35	((al or aluminum) near2 (alloy or base or based or balance)) and (sc or scandium or si or silicon or ti or titanium or hf or hafnium) and ((grain or size) near2 ("mu.m" or "mu" or "mu." or micron or micrometer or ".mu.m" or ".mu." or "mum" or mu.m or \$1"mu.m")) and ((sputter\$4 or physical or vapor) near3 target) and (148/\$.ccls. or 420/\$.ccls.) not ((148/437,415.ccls. or 420/548,552.ccls.) and (sc or scandium or si or silicon or ti or titanium or hf or hafnium) and (grain or size near2 ("mu.m" or "mu" or "mu." or micron or micrometer or ".mu.m" or ".mu." or "mum" or mu.m or \$1"mu.m")) and ((sputter\$4 or physical or vapor) near3 target))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/20 16:46
-	7	c22c021\$.ipc. and (sc or scandium or si or silicon or ti or titanium or hf or hafnium) and (ecae or ((equal or channel) near2 (extrusion or extruded or extrude))) and ((grain or size) near2 ("mu.m" or "mu" or "mu." or micron or micrometer or ".mu.m" or ".mu." or "mum" or mu.m or \$1"mu.m")) and ((sputter\$4 or physical or vapor) near3 target)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/20 17:08